

U.S. Department of Commerce, Patent and Trademark Office				Docket No.		Serial No.	
(PTO Form 1449 modified)				AMAT/2966/PDD/KPU1/JW		09/165,248	
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT				Applicant			
(Use several sheets if necessary)				Rathi et al.			
				Filing Date		Group	
				October 1, 1998		2811 823	

OIPE JCIS  
 MAY 05 2000  
 PATENT & TRADEMARK OFFICE

U.S. Patent Documents							
*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
G	AA	5,741,626	04/21/1998	Jain et al.	430	314	04/15/1996
	AB	4,951,601	08/28/1990	Maydan et al.	118	719	06/23/1989
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

Foreign Patent Documents							Translation	
		Document Number	Date	Country	Class	Subclass	Yes	No
G	AK	EP0725440A2	08/07/1996	Europe	<del>H01L</del>	<del>23/532</del>	X	
	AL							
	AM							
	AN							
	AO							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
G	AP	Ogawa et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K1 Factor", <i>Proceedings of the SPIE. Optical/Laser Microlithography V</i> , vol. 1674, 1992, pages 362-375.
G	AQ	Dijkstra et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", <i>Proceedings of SPIE Optical/Laser Microlithography, Bellingham, SPIE</i> , vol. 1927, pages 275-286.
G	AR	PCT International Search Report dated March 9, 2000, for PCT/US99/22424.
G	AS	PCT Partial International Search Report dated March 21, 2000, for PCT/US99/22317.

Examiner PEARSON	Date Considered 4/21/01
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.